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TECHNICAL DATA SHEET

## Siltech<sup>®</sup> C-241

### Description

**Siltech<sup>®</sup> C-241** is a polyether siloxane copolymer that is primarily used to eliminate cratering and improve slip.

### Typical Properties

Appearance	Clear Liquid
Specific gravity at 25°C	1.01
Colour, Gardner	2 Max
Active Content %	95
Viscosity at 25°C, cps	1,500
Refractive Index at 25°C	1.435
Diluents	Isopropanol, Butyl Glycol, Butyl Acetate, Xylene.

### Application & Uses

**Siltech<sup>®</sup> C-241** is used in solvent-based, water-based and energy curing coatings and inks formulations to eliminate cratering, improve slip, anti-blocking and flow. It also prevents pigment floatation and provides mar resistance.

The amount of **Siltech<sup>®</sup> C-241** used ranges from 0.1-1.0% weight percent based on total the formulation. It can be incorporated in any stage of production processes or added during final let-down.

### Shelf Life

When stored in the original, unopened containers between 10 and 40°C, **Siltech<sup>®</sup> C-241** has a shelf life of 36 months from date of manufacture.

### Packaging

**Siltech<sup>®</sup> C-241** is supplied in 20kg pails and 200kg drums.

### Legal Disclaimer

Siltech Corporation believes that the information in this technical data sheet is an accurate description of the typical uses of the product. Siltech Corporation, however, disclaims any liability for incidental or consequential damages, which may result from the use of the product that are beyond its control. Therefore, it is the user's responsibility to thoroughly test the product in their particular application to determine its performance, efficacy and safety. Nothing contained herein is to be considered as permission or a recommendation to infringe any patent or any other intellectual property right.

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